

L Number	Hits	Search Text	DB	Time stamp
1	1529	(dual adj damascene) and (photo\$lresist or resist or photo\$lensitive)	USPAT	2004/03/17 15:52
2	89	((dual adj damascene) and (photo\$lresist or resist or photo\$lensitive) ) and (plug with (resin or polymer or photo\$lresist or photo\$lensitive))	USPAT	2004/03/17 16:52
3	4	("6174796"   "6319815"   "6323121"   "6380073").PN.	USPAT	2004/03/17 15:57
4	21	Chang-Weng.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/17 17:00
-	1529	(dual adj damascene) and (photo\$lresist or resist or photo\$lensitive)	USPAT	2004/03/17 15:51
-	1345	((dual adj damascene) and (photo\$lresist or resist or photo\$lensitive)) and (liner or conformal or sidewall or barrier)	USPAT	2004/03/17 09:14
-	736	((((dual adj damascene) and (photo\$lresist or resist or photo\$lensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop)))	USPAT	2004/03/17 09:15
-	709	(((((dual adj damascene) and (photo\$lresist or resist or photo\$lensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via	USPAT	2004/03/17 09:15
-	390	(((((dual adj damascene) and (photo\$lresist or resist or photo\$lensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)	USPAT	2004/03/17 09:17
-	372	((((((dual adj damascene) and (photo\$lresist or resist or photo\$lensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)	USPAT	2004/03/17 09:17
-	370	((((((dual adj damascene) and (photo\$lresist or resist or photo\$lensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)) and @ay<=2002	USPAT	2004/03/17 09:18
-	342	((((((dual adj damascene) and (photo\$lresist or resist or photo\$lensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)) and @ay<=2001	USPAT	2004/03/17 11:36
-	1	6358842.pn.	USPAT	2004/03/17 11:35
-	11	("5536681"   "5540812"   "5759906"   "5821168"   "5976626"   "5985762"   "6024887"   "6100181"   "6100184"   "6150723"   "6194321").PN.	USPAT	2004/03/17 11:35

-	111	(((((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)) and @ay<=2001) and (conformal\$3)	USPAT	2004/03/17 11:36
-	26	(((((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)) and @ay<=2001) and (conformal\$3)) and @py<=2000	USPAT	2004/03/17 11:40
-	85	(((((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)) and @ay<=2001) and (conformal\$3)) not (((((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)) and @ay<=2001) and (conformal\$3)) and @py<=2000)	USPAT	2004/03/17 15:50
-	5	("5877084"   "6054384"   "6100184"   "6184128"   "6211092").PN.	USPAT	2004/03/17 11:48